



Session Title:	[ME1] EUV Lithography I
Session Date:	November 20 (Mon.), 2023
Session Time:	13:00-14:30
Session Room:	Room E (Sidney Room, 2F)
Session Chair:	Prof. Sangsul Lee (POSTECH, Korea)

[ME1-1] [Invited]

13:00-13:30

EUV R&D Activity at NewSUBARU

Takeo Watanabe, Tetsuo Harada, and Shinji Yamakawa (Univ. of Hyogo, Japan)

[ME1-2] [Invited]

13:30-14:00

Synchrotron Based Actinic EUV Metrology and Inspection Technologies

Sangsul Lee, Jiho Kim, Geonhwa Kim, Nam Hyeon Kim, Gwiyoung Shin, Dong Gun Lee, Byung Gook Kim, Jang-Hui Han, Sojeong Lee, Juho Hong, Jun Ho Ko, Ji Yeon Kim, Minwoo Kim, Beom Jun Kim, Sangbong Lee, Se-Jin Kwon, and Docheon Ahn (POSTECH, Korea)

[ME1-3] [Invited]

14:00-14:30

Development of High-Efficiency EUV Zoneplate for Advanced EUV Lithography Equipment

Jebum Yoon, Taegon Park, Yoonseo Lee, Jihye Kim, and Donggun Lee (ESOL Inc, Korea)